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**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Hiromoto OHNO, et al.

Appln. No.: 10/088,306

Confirmation No.: 2926

Filed: March 18, 2002

For: **CLEANING GAS FOR SEMICONDUCTOR PRODUCTION EQUIPMENT**

**RECEIVED**

JUL 27 2004

TECHNOLOGY CENTER R3700

Docket No: Q60716

Group Art Unit: 3749

Examiner: Kathryn S. O Malley

**RESPONSE TO RESTRICTION REQUIREMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Responsive to the outstanding Restriction Requirement of July 13, 2004, Applicant elects Group I, claims 1-22 (gas composition) for prosecution, without traverse. Applicants reserve the right to request rejoinder of method claims including all the limitations of any allowable product claim pursuant to MPEP §821.04. Applicants also reserve the right to file a Divisional Application directed to the non-elected subject matter.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,

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WASHINGTON OFFICE

**23373**

CUSTOMER NUMBER

Date: July 23, 2004